

第83回応用化学科セミナー

分子動力学法を用いた 無機多孔体に関する研究

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内容

無機多孔質体・分子動力学法

ゼオライトの熱的挙動に関する研究
第20回ゼオライト研究発表会 (東京, 2004)

均一メソポーラスシリカのモデリング
14th International Zeolite Conference
(Cape Town, 2004)

無機多孔質体

細孔径による多孔体の分類 (IUPAC)

マイクロ孔 (diameter < 2 nm) メソ孔 (2 nm < diameter < 50 nm) マクロ孔 (diameter > 50 nm)

ゼオライト 均一メソ多孔体
活性炭 Xerogel Aerogel Porous Glasses
Pillared Clays

均一な細孔径分布

ゼオライト 均一メソ多孔体
ミクロ孔を持つ結晶構造 界面活性剤等のミセルを
テンプレートとした細孔形成

Zeolites

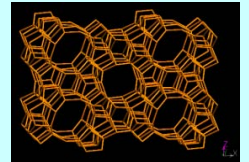
結晶性の多孔質アルミケイ酸塩の総称
種々の骨格構造を有する

(M_nAl_nSi_{1-n}O₂•H₂O)

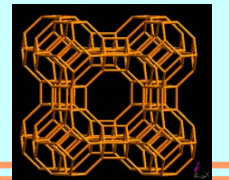
MFI (ZSM-5)

構造コード

ABW	ACD	AFI	AEI	AEN	AET	APG	APF	AFN	AFO	AFR	AFS
AFI	AFX	AFY	AHT	ANA	APC	APD	AST	ASV	ATN	ATQ	ATP
ATT	ATY	AWO	AWW	BCT	BFA	BFC	BFD	BGG	BPH	BRE	CAN
CAS	CDP	CFI	DGF	DGS	CHA	CHI	CLO	CON	CZE	DAC	DDR
DFO	DET	DGH	DGN	EAB	EPL	EMT	ERL	ERL	FSS	ETR	FUO
FAL	FER	FRA	GB	GHU	GMF	GOO	GOO	HFI	HFR	ISY	ITL
ITR	ITW	IBR	IKW	JRW	KFI	LAU	LEV	LJO	LOS	LOX	LTA
LTA	LTN	MAR	MAG	MFI	MEL	MFT	MFR	MFI	MPS	MON	MOB
MSO	MIF	MTA	MTT	MTW	MWW	NAB	NAT	NES	NOH	NOV	OBW
OFI	OSI	OSO	PAB	PAL	PHI	POH	RHO	ROS	ZHO	RSS	RTE
RTH	RUL	RWB	RBY	SAD	SAS	SAT	SAY	SBE	SBS	SBL	SFL
SFF	SFG	SFH	SEN	SFO	SGI	SOD	SOS	SSY	STF	SHI	STL
TER	THO	TOS	TSC	TFI	TFI	TOZ	USI	UTR	VEI	YFI	YSI
YSY	WEI	WEN	YUG	ZON							



LTA (zeolite A)



古典分子動力学 (MD) 法

古典力学に由来した運動方程式の計算

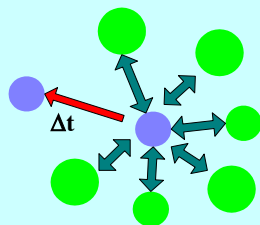
原子間の相互作用の計算

各原子の速度と位置

構造、物性

粒子 (原子) 数 数千~数万)

電子状態や化学結合は扱えない)



SiO₂の原子間相互作用モデル

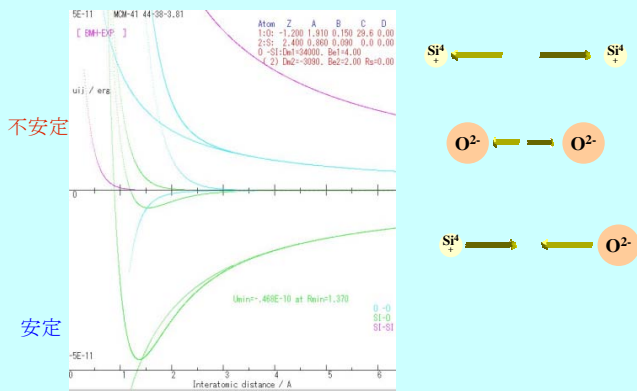
2中心力モデル

$$U_{ij}(r_{ij}) = \frac{Z_i Z_j e^2}{4\pi\epsilon_0 r_{ij}} + f_0 (b_i + b_j) \exp\left[\frac{(a_i + a_j - r_{ij})}{(b_i + b_j)}\right] - c_i c_j / r_{ij}^6$$

$$+ D_{1j} \exp(-\beta_{1j} r_{ij}) + D_{2j} \exp(-\beta_{2j} r_{ij})$$

	Z	a	b	c
O	-1.2	1.91	0.15	29.6
Si	2.4	0.86	0.09	0.0
	D ₁	β ₁	D ₂	β ₂
O-Si	31000	5.0	-3090	2.5

Potential Curves of SiO₂



ゼオライトの熱的挙動に関する研究

背景

ゼオライトの分子ふるい作用
 ゼオライトの細孔径に依存

ゼオライトの細孔径
 結晶構造から決定 振動により変動
 細孔径の温度変化 ?



分子動力学法の利用

SiO₂ゼオライトの構造変化

負の熱膨張

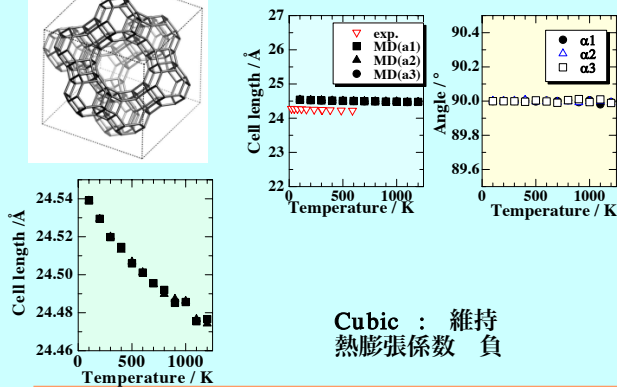
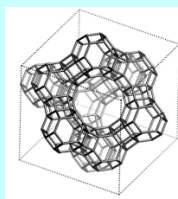
Faujasite (Attfield and Sleight, 1998)
 Chabazite and ITQ-4 (Woodcock and Lightfoot, 1999)
 MWW, ITE, ISV, STF etc.

- Siliceous Ferrierite (Bull et al., 2003)
 Pnnm \leftrightarrow Immm 負の熱膨張
- MFI monoclinic \leftrightarrow orthorhombic

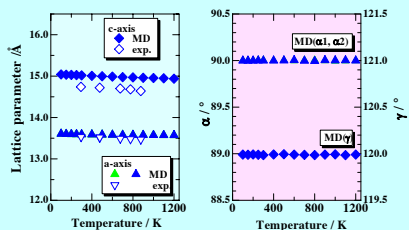
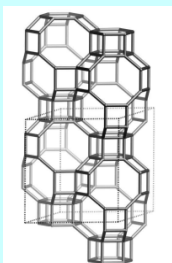
目的

- SiO₂組成ゼオライトの構造熱的挙動
- 格子定数変化
 Faujasite, Chabazite, ITQ-4, ZSM-11
- 細孔径変化
 ZSM-11

Faujasiteの構造変化

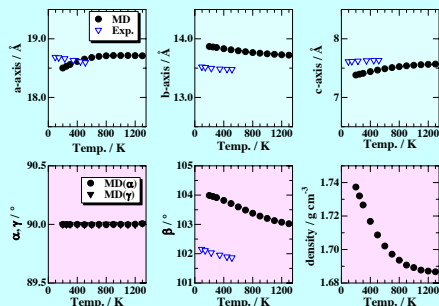
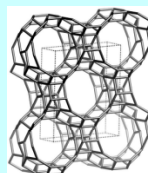


Chabaziteの構造変化



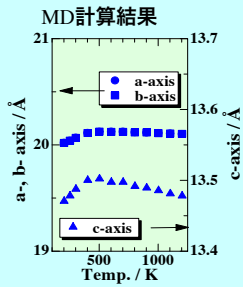
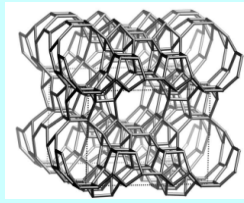
Hexagonal 維持
 熱膨張係数 負

ITQ-4の構造変化



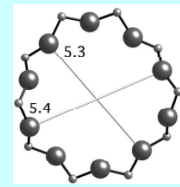
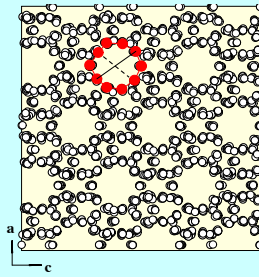
ZSM-11の構造変化

計算サイズ unit cell 12個 (2x2x3)



400K 程度で対称性に変化 相転移?) (Fyfe et al., 1989)

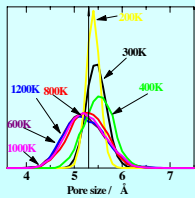
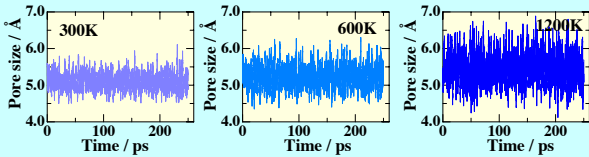
ZSM-11の細孔構造



酸素イオンサイズ 2.7Å

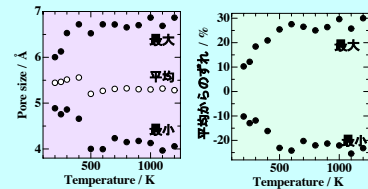
ZSM-11の酸素原子の位置

細孔の熱挙動

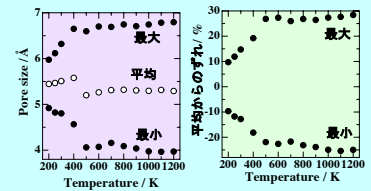


細孔径
400K まで 増加
600K 以上 分布が類似

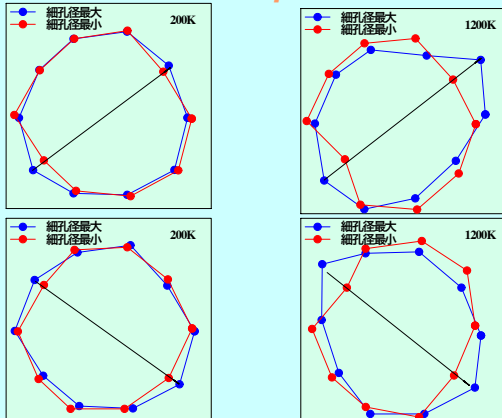
ZSM-11の細孔径変化



12 Unit cellの平均値



細孔のSnap shot



SiO₂ゼオライトの熱的挙動

Faujasite, Chabazite, ITQ-4
負の熱膨張を再現

ZSM-11

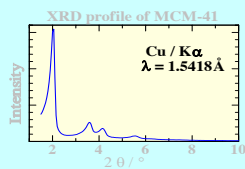
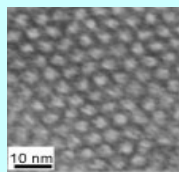
500Kから負の熱膨張
最大細孔径 400Kまで 大きく増加
600K以上 ほぼ一定

均一メソポーラスシリカのモデリング

高表面積
均一細孔径
細孔構造の規則的な配列

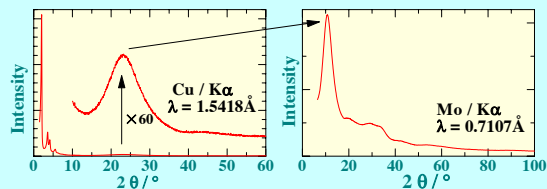
多様な合成法

- Cationic ion ($C_nH_{2n+1}N(CH_3)_3$ ion)
 - MCM-41
 - FSM-16 - hexagonal phase
- Block copolymer (PEO-PPO-PEO)
 - SBA-15



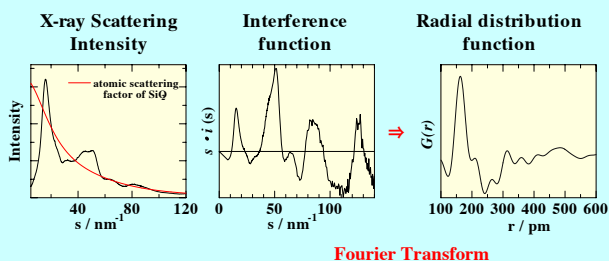
Pore Wall of Mesoporous silica

Amorphous $SiO_{2-x}(OH)_{2x}$
Structure Analysis ⇒ NMR, IR, EXAFS

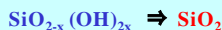


Radial distribution function analysis using X-ray diffraction methods

Procedure of radial distribution function analysis



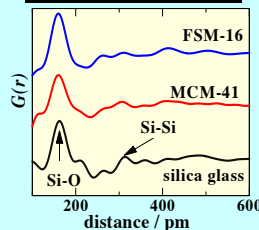
Composition of mesoporous silica



Intensity of X-ray scattering from H atom ⇒ little

Comparison of structure to Silica glass

Correlation Function



Results of XRD Analysis

Sample	r_{Si-O}^*/pm	r_{Si-Si}^*/pm	references
Silica glass	163	314	[4]
MCM-41	161	307	[4]
	160	305	[2]
	160	300	[3]
FSM-16	160	310	[4]

- [1] Mozzi and Warren (1969)
- [2] Pophal et al. (1997)
- [3] Pophal and Fuess (1999)
- [4] Ookawa et al. (2001)

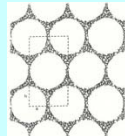
Si-O distance MCM-41, FSM-16 = Silica glass

Si-Si distance MCM-41, FSM-16 < silica glass

Discussion in detail with structure model

Previous works - Modeling of MCM-41 using MD

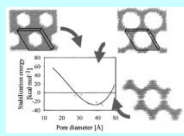
Feuston and Higgins, 1994



Parallel two micelles packed in a hexagonal arrangement

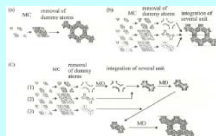
Relaxation at 900K

Klestorfer et al., 2001



Modeling from quartz structure setting H⁺ on the surface

Oumi et al., 2002



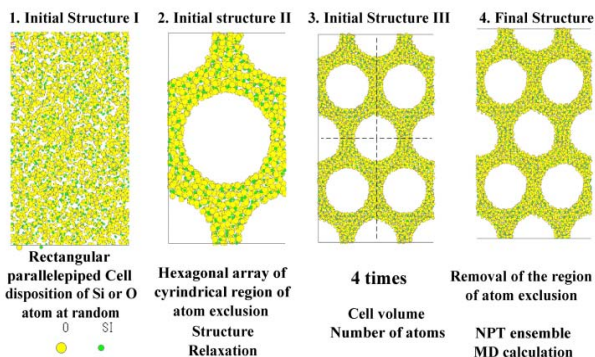
Modeling with combination of MD and MC methods

The differences of the structure between the pore wall of MCM-41 and silica glass have not been discussed.

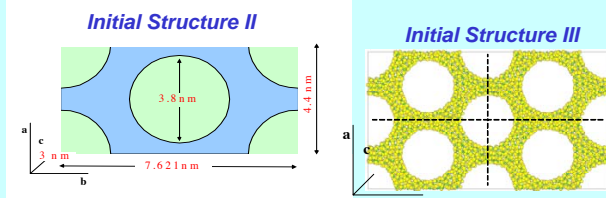
Aim of this work

MCM-41 type silica was made under the different condition and the comparison of our experimental results.

Modeling method of MCM-41 type mesoporous silica by using molecular dynamics



Initial Structure II and III



$b/a = \sqrt{3}$

Hexagonal array of the cylindrical region of atom exclusion

MD calculation of SiO₂ melt under NVT ensemble

Relaxation 2500K \Rightarrow 300K

MD cell volume \Rightarrow 4 times

Number of atoms \Rightarrow 4 times

MD cell : a = 8.8 nm
b = 10.4 nm
c = 3.0 nm

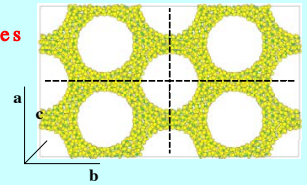
Removal of the region of atom exclusion

NPT ensemble (300 K, 0.1MPa)
200000 steps (40 ps)

Detail of the Initial Structure III

MD cell volume \Rightarrow 4 times
Number of atoms \Rightarrow 4 times

MD cell : a = 8.8 nm
b = 10.4 nm
c = 3.0 nm



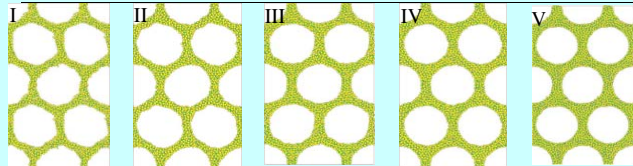
Removal of the region of atom exclusion

MD calculation: NPT ensemble (300 K, 0.1MPa)

200000 step (40 ps)

Modeling Conditions and Results

model	Initial Condition		Final structure (after the MD calculation)			
	Number of SiO ₂ unit	Density /g cm ⁻³	Density /g cm ⁻³	a axis /nm	b axis /nm	c axis /nm
I	653	0.65	0.69	8.65	14.89	2.93
II	784	0.78	0.81	8.59	15.06	2.95
III	849	0.84	0.89	8.63	15.00	2.93
IV	996	0.99	1.00	8.66	15.28	2.98
V	1246	1.42	1.20	8.87	15.29	3.04

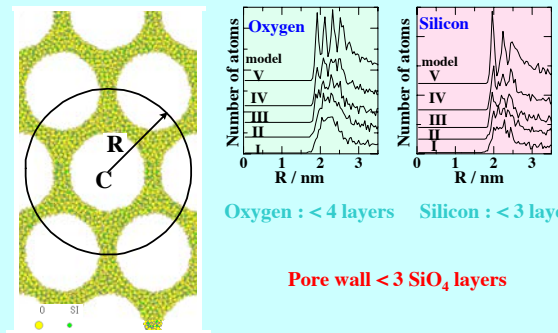


Cross-section shapes of mesopore

Model I, Model II, Model III Hexagon
Model IV, Model V Circle

Increasing the number of atom (Wall thickness)

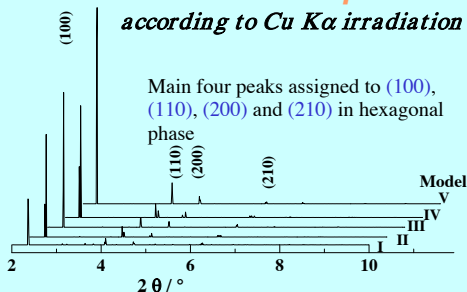
Distribution of Si and O atoms



Oxygen : < 4 layers Silicon : < 3 layers

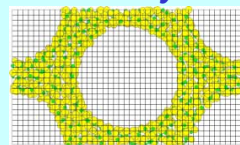
Pore wall < 3 SiO₂ layers

Simulated XRD profiles according to Cu K α irradiation

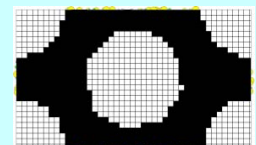


Relative peak intensity of (110) or (200), to (100)
model II or III > model V.

Analysis of Pore Structure

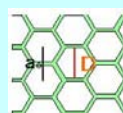


Formation of 3D grid in the MD cell



Determination of nature of each grid point
atomic cell included in the Van der Waals sphere (Si:41 pm O:140 pm)
pore cell

Surface Area: Sum of Interfacial area between atomic cell and pore cell
Mean pore diameter: Estimated by pore volume and length of c-axis



Wall thickness = $a_0 - D$

Results of pore structure analysis and simulated XRD

Model	I	II	III	IV	V
Surface area / m ² g ⁻¹	1626	1181	1072	870	686
Pore volume / cm ³ g ⁻¹	0.78	0.63	0.55	0.46	0.36
Pore diameter / nm	3.33	3.26	3.19	3.15	3.08
Wall density / g cm ⁻³	1.50	1.70	1.76	1.91	2.15
a ₀ / nm	4.32	4.32	4.32	4.36	4.42
Wall thickness / nm	0.99	1.06	1.13	1.21	1.34

MCM-41 Sonwane et al., (1999)

Pore diameter/ nm	3.8
Surface area / m ² g ⁻¹	1240
Pore volume / cm ³ g ⁻¹	0.93

Surface Area

Model I, II, III > 1000 m²g⁻¹

Wall thickness

Experimental value by TEM
(Kruk et al.,2000)
ca. 1 -1.3 nm

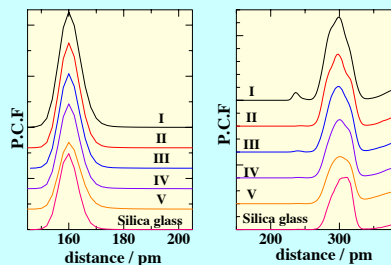
Pore Volume

Simulation < Experiment

Calculation of pore volume will need to an improved program

$$a_0 = 2 / \sqrt{3} \times d(100)$$

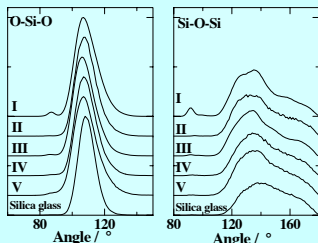
Pair correlation functions(PCF) of Si-O and Si-Si



Si-O : almost the same Si-Si : MCM-41 < silica glass

These results support strongly our experimental results

Distribution of bond angle of O-Si-O and Si-O-Si



O-Si-O angle

Internal angle of SiO₄ tetrahedra

Angle: MCM-41 < silica glass

Width of distribution:

MCM-41 > silica glass

SiO₄ tetrahedra in the pore wall

⇒ strained

Si-O-Si angle

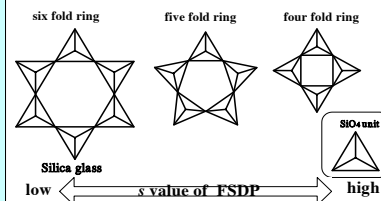
Angle between neighboring two SiO₄ tetrahedra

Distribution shift to low angle region compared to silica glass

Model I
Si-O-Si 87°
O-Si-O 92°
Si-Si (from PCF) 236 pm
⇒ No realistic model

Medium range order of amorphous silica

Siloxane ring size



Summary

Modeling of MCM-41 type porous silica was performed by molecular dynamics simulation.

Some models have reproduced ca. 3 nm diameter and more than 1000 m²g⁻¹ surface area.

It is clear that MCM-41 type silica model have same Si-O interatomic distance and shorter Si-Si interatomic distance compared to silica glass.

MD calculation revealed that the mean Si-O-Si bond angle in MCM-41 type silica is smaller than that in silica. This result supports our experimental results.

喜望峰

